

Title (en)

Patterning apparatus and patterning method using the same

Title (de)

Mustererzeugungsvorrichtung und Mustererzeugungsverfahren damit

Title (fr)

Appareil de formation de motifs et procédé de formation de motifs l'utilisant

Publication

**EP 2314461 A2 20110427 (EN)**

Application

**EP 10187544 A 20101014**

Priority

KR 20090099104 A 20091019

Abstract (en)

A patterning apparatus (10) includes a first die (100) and a second die (200) to press a metal member (20), a liquid type medium containing unit (700) to contain a liquid type medium (700A), a three-dimensional forming unit (300) formed at at least one of the first (100) and second (200) dies, the three-dimensional forming unit (300) contacting the metal member when the medium presses the metal member (20), and a pattern processing unit (400) formed at the three-dimensional forming unit (300). A patterning method includes providing a metal member (20) to a first die (100), moving a second die (200) downward to the top of the metal member (20), providing a liquid type medium (700A) to the metal member (20), pressing the metal member (20) using the medium (700A) such that the metal member (20) contacts a three-dimensional forming unit (300) formed at at least one of the first (100) and second (200) dies, and pressing the metal member (20) such that the metal member (20) contacts a pattern processing unit (400) formed at the three-dimensional forming unit (300).

IPC 8 full level

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CPC (source: EP)

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Citation (applicant)

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